

Custom Ptfе Laboratory Cleaning Basket Carrier High Purity Acid Base Resistant Wafer Holder Low Background Contamination Free Chemical Bath Rack

Item Number: PL-CP268



Introduction

Discover high-purity custom PTFE cleaning basket carriers designed for semiconductor and trace analysis. These acid-resistant racks ensure zero leaching and ultra-low background levels, providing reliable performance in the most demanding chemical environments for precision laboratory cleaning processes.

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Application	Description	Key Benefit
Semiconductor Wafer Cleaning	Securely holding silicon wafers during RCA cleaning or HF etching processes in cleanroom environments.	Prevents metallic contamination and ensures uniform chemical exposure.
Trace Metal Analysis	Cleaning and leaching of labware used for ICP-OES and ICP-MS sample preparation to reach ppt-level purity.	Eliminates background interference from the vessel material itself.
Battery Research	Handling anode and cathode materials during electrolyte immersion or chemical treatment phases.	Resistance to aggressive organic solvents and lithium salts.
Pharmaceutical Sterilization	Carrying glass vials or precision components through high-temperature or chemically aggressive sterilization cycles.	Maintains purity and prevents surface adsorption of active ingredients.
Aerospace Component Degreasing	Holding precision-machined alloy parts during deep-cleaning cycles in harsh chemical de-greasers.	Long-term durability in industrial-strength cleaning reagents.
Solar Cell Fabrication	Supporting photovoltaic substrates during wet chemical processing and texturing stages.	High temperature resistance and chemical compatibility with etching agents.
Geological Sample Prep	Digesting and cleaning mineral samples using concentrated hydrofluoric acid for elemental determination.	Safe handling in hazardous acid environments without vessel degradation.

Specification Category	Parameter Details for PL-CP268	Values / Capabilities
Material Properties	Primary Construction Material	Virgin High-Purity PTFE (Polytetrafluoroethylene)
	Trace Element Background	Ultra-Low (Suitable for PPT-level analysis)
	Chemical Resistance	Universal (Except molten alkali metals/fluorine)
	Water Absorption	<0.01%
Physical Dimensions	Configuration	Fully Customizable to Client Specifications
	Sizing Options	Bespoke designs for 2", 4", 6", 8", 12" wafers or custom labware
	Handling Features	Optional integrated handles, extendable arms, or locking lids
Thermal Limits	Maximum Operating Temperature	260°C (500°F)
	Minimum Operating Temperature	-200°C (-328°F)

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Manufacturing Details	Fabrication Method	High-Precision CNC Machining
	Surface Roughness	Ra 0.4 - 0.8 μm (Standard) / Polished options available
	Item Number Reference	PL-CP268